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U.S. UTILITY Patent Application

PATENT NUMBER and
ISSUE DATE

912

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10025798	12/26/2001	216		1746	

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****CONTINUING DATA VERIFIED**

**** FOREIGN APPLICATIONS VERIFIED:**
REPUBLIC OF KOREA 2001-12629 03/12 2001

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed <input type="checkbox"/> yes <input type="checkbox"/> no 35 USC 119 conditions met <input type="checkbox"/> yes <input type="checkbox"/> no Verified and Acknowledged Examiner's initials		ATTORNEY DOCKET NO 030681-341

TITLE : Method of reducing notching during reactive ion etching

NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
ISSUE FEE Amount Due Date Paid		Assistant Examiner	Total Claims Print Claim for O.G.
			DRAWING Sheets Drwg. Figs. Drwg. Print Fig.
<input type="checkbox"/> TERMINAL DISCLAIMER		Primary Examiner	Application Examiner
		PREPARED FOR ISSUE	
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